



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Ramkumar SUBRAMANIAN, et al.
Title: TWO MASK PHOTORESIST EXPOSURE PATTERN
FOR DENSE AND ISOLATED REGIONS
Appl. No.: Unassigned
Filing Date: June 25, 2001
Examiner: Unassigned
Art Unit: Unassigned

UTILITY PATENT APPLICATION
TRANSMITTAL

Commissioner for Patents
Box PATENT APPLICATION
Washington, D.C. 20231

Sir:

Transmitted herewith for filing under 37 C.F.R. § 1.53(b) is the nonprovisional utility patent application of:

Ramkumar SUBRAMANIAN
Scott A. BELL
Todd P. LUKANC
Marina V. PLAT
Uzodinma OKOROANYANWU
Hung-Eil KIM

Enclosed are:

- [X] Specification, Claims, and Abstract (18 pages).
- [X] Formal drawings (5 sheets, Figures 1-7).
- [X] Declaration and Power of Attorney (4 pages).
- [X] ✓ Assignment of the invention to ADVANCED MICRO DEVICES, INC.
- [X] Assignment Recordation Cover Sheet.
- [X] Proprietary Information Disclosure Statement with a copy of (2) U.S. Patent Applications.

☒ Request for application not to be published with certification under 35 USC 122(b)(2)(B)(i).

The filing fee is calculated below:

	Claims as Filed	Included in Basic Fee	Extra Claims	Rate	Fee Totals
Basic Fee				\$710.00	\$710.00
Total Claims:	32	- 20	= 12	x \$18.00	= \$216.00
Independents:	3	- 3	= 0	x \$80.00	= \$0.00
If any Multiple Dependent Claim(s) present:			+	\$270.00	= \$0.00
				SUBTOTAL:	= \$926.00
<input type="checkbox"/> Small Entity Fees Apply (subtract 1/2 of above):					= \$0.00
				TOTAL FILING FEE:	= \$926.00
Assignment Recordation Fee:			+	\$40.00	= \$40.00
				TOTAL FEE	= \$966.00


- ☒ A check in the amount of \$966.00 to cover the filing fee and fee for recordation of Assignment is enclosed.
- ☒ The Commissioner is hereby authorized to charge any additional fees which may be required regarding this application under 37 C.F.R. §§ 1.16-1.17, or credit any overpayment, to Deposit Account No. 19-0741. Should no proper payment be enclosed herewith, as by a check being in the wrong amount, unsigned, post-dated, otherwise improper or informal or even entirely missing, the Commissioner is authorized to charge the unpaid amount to Deposit Account No. 19-0741.

Please direct all correspondence to the undersigned attorney or agent at the address indicated below.

Respectfully submitted,

Date June 25, 2001

FOLEY & LARDNER
Washington Harbour
3000 K Street, N.W., Suite 500
Washington, D.C. 20007-5109
Telephone: (202) 672-5407
Facsimile: (202) 672-5399

By  Key No 43445

For David A. Blumenthal
Attorney for Applicant
Registration No. 26,257

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Ramkumar SUBRAMANIAN, et al.
Title: TWO MASK PHOTORESIST EXPOSURE PATTERN
FOR DENSE AND ISOLATED REGIONS
Appl. No.: Unassigned
Filing Date: 06/25/2001
Examiner: Unassigned
Art Unit: Unassigned

REQUEST AND CERTIFICATION UNDER 35 U.S.C. 122(b)(2)(B)(i)

Commissioner for Patents
Washington, D.C. 20231

Sir:

Applicants hereby certify that the invention disclosed in the attached application has not and will not be the subject of an application filed in another country, or under a multilateral agreement, that requires publication at eighteen months after filing.


Applicants hereby request that the attached application not be published under 35 U.S.C. 122(b).

Respectfully submitted,

Date June 25, 2001

FOLEY & LARDNER
Washington Harbour
3000 K Street, N.W., Suite 500
Washington, D.C. 20007-5109
Telephone: (202) 672-5407
Facsimile: (202) 672-5399

By

 Reg. No. 83,445

for David A. Blumenthal
Attorney for Applicant
Registration No. 26,257